

측온 저항체의 Pt 박막 특성 연구

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요업기술원 전자부품소재본부 전자소재팀²

Study on Pt thin film property of Resistance Temperature Detect

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Abstract : Platinum Thin films were deposited on Al₂O₃ by Rf magnetic Sputtering. The physical and electrical characteristics of these films were analyzed under various deposition conditions(Ar gas pressure, input power, substrate temperature.) and annealing condition. The deposition rate was increased with increasing the input power but not increased linear. In the other factor, The Pt thin films property was associated with resistance. so lower resistance had more and more good Pt thin films condition. For the purpose of this study, we will get the best Pt thin film characteristics

Key Words : Platium, RTD, Thin films, Rf magnetic Sputtering